Supporting Information

Growth Kinetics of the Adsorbed Layer of Poly(2-vinylpyridine) – An indirect observation of desorption of polymers from substrates.

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Figure S1: AFM phase contrast image for the adsorbed layer of P2VP solvent leached from a ca. 200 nm thick film which was annealed at 413 K (140 °C, T_g +42 K) for 336 h.



Figure S2: Time dependence of the thickness of the adsorbed layer for the annealing temperature of 383 K (110 °C, T_g+12 K). The dashed line is a fit of the initial states of the growth kinetics with a power law $\sim (\frac{t}{t_{growth}})^{\sigma}$ as described in the manuscript with σ =1±0.001 and t_{growth}=(8.34±0.2) h. The solid line is a guide for the eyes. The dashed-dotted arrow indicates how t_c was estimated.



Figure S3a: Time dependence of the thickness of the adsorbed layer for the annealing temperature of 403 K (130 °C, T_g+32 K). The dashed line is a fit of the initial states of the growth kinetics with a power law $\sim (\frac{t}{t_{growth}})^{\sigma}$ as described in the manuscript with σ =0.49±0.0503 and t_{growth}=(0.367±0.17) h. The dotted line indicates the linear growth regime. The solid line is a guide for the eyes. The dashed-dotted arrow indicates how t_c was estimated.



Figure S3b: Time dependence of the thickness of the adsorbed layer for the annealing temperature of the data given in Figure S3a in the time range from 0 to 80 h. The dashed line is a fit of the initial states of the growth kinetics with a power law $\sim (\frac{t}{t_{growth}})^{\sigma}$ as described in the manuscript with σ =0.49±0.0503 and t_{growth}=(0.367±0.17) h. The dotted line indicates the linear growth regime.



Figure S3c: Residual plot for the power law fit given in Figure S3b.



Figure S4a: Time dependence of the thickness of the adsorbed layer for the annealing temperature of 413 K (140 °C, T_g+42 K). The dashed line is a fit of the initial states of the growth kinetics with a power law $\sim (\frac{t}{t_{growth}})^{\sigma}$ as described in the manuscript with σ =0.328±0.0185 and t_{growth}=(0.0311±0.0185) h. The dotted line indicates the linear growth regime. The solid line is a guide for the eyes.



Figure S4b: Residual plot for the power law fit given in Figure S3a.



Figure S5: Power exponent σ versus temperature. The line is a linear regression to the data.